

Amendment and Response

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Serial No.: 09/651,702

Confirmation No.: 2471

Filed: August 30, 2000

For: SUPERCRITICAL COMPOSITIONS FOR REMOVAL OF ORGANIC MATERIAL AND METHODS OF USING SAME

In the Claims

Please add new claims 49-54. The new claims are provided below in clean form.

For convenience, all pending claims, including those added hereby, are provided in Appendix A.

49. (New) A composition comprising sulfur trioxide (SO₃) in a supercritical state, wherein the composition is a composition for removing exposed organic material from an object.

50. (New) A composition comprising sulfur trioxide (SO₃) in a supercritical state and an oxidizer, wherein the composition is a composition for removing exposed organic material from an object.

51. (New) A composition comprising:

a first component selected from the group consisting of carbon dioxide (CO₂), ammonia (NH₃), H₂O, nitrous oxide (N₂O), carbon monoxide (CO), nitrogen (N₂), helium (He), neon (Ne), argon (Ar), krypton (Kr), and xenon (Xe);

a second component selected from the group consisting of sulfur dioxide (SO₂), nitrous oxide (N₂O), NO, NO₂, ozone (O₃), hydrogen peroxide (H₂O₂), F₂, Cl₂, Br₂, and oxygen (O₂); and sulfur trioxide (SO₃) in a supercritical state, wherein the composition is a composition for removing exposed organic material from an object.

52. (New) A composition comprising sulfur trioxide (SO₃) in a supercritical state, wherein the composition is a composition for removing exposed organic material from a substrate assembly.

53. (New) A composition comprising sulfur trioxide (SO₃) in a supercritical state and an oxidizer, wherein the composition is a composition for removing exposed organic material from a substrate assembly.

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54. (New) A composition comprising:

a first component selected from the group consisting of carbon dioxide (CO₂), ammonia (NH₃), H₂O, nitrous oxide (N₂O), carbon monoxide (CO), nitrogen (N₂), helium (He), neon (Ne), argon (Ar), krypton (Kr), and xenon (Xe);

a second component selected from the group consisting of sulfur dioxide (SO₂), nitrous oxide (N₂O), NO, NO₂, ozone (O₃), hydrogen peroxide (H₂O₂), F₂, Cl₂, Br₂, and oxygen (O₂); and

sulfur trioxide (SO₃) in a supercritical state, wherein the composition is a composition for removing exposed organic material from a substrate assembly.
